



The Influence of Surface Effects on the Simulation of 1.3 μ m InGaAsN Edge-Emitting Lasers

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Presentation Outline



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- Boundary condition models
- Surface Fermi-level pinning
- Simulation tool
- Dilute nitride lasers
- Simulation results
- Conclusions and outlook

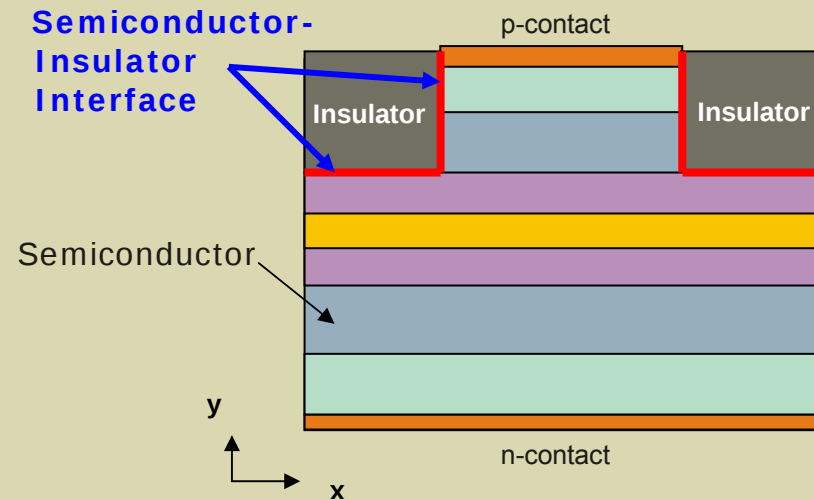
Semiconductor-insulator boundary condition models usually employ a combination of the following assumptions:

- Fixed surface charge

$$\varepsilon_0 \varepsilon_s \frac{\partial \phi}{\partial \mathbf{n}} = Q_s$$

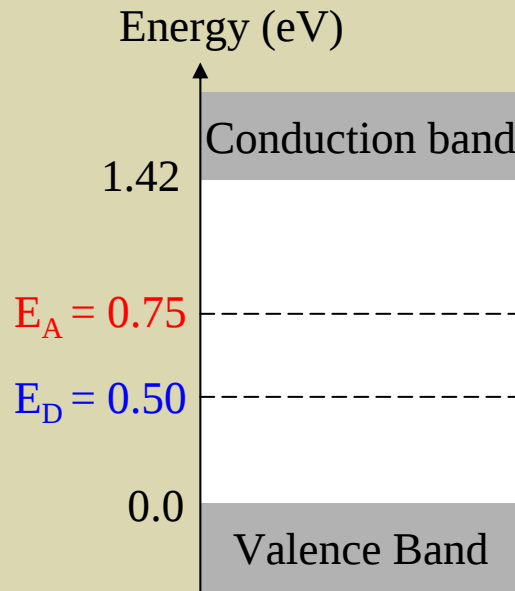
- Fixed surface recombination velocity

$$\mathbf{n} \cdot \mathbf{J}_n = -qv_{sr}(np - n_0 p_0)$$
$$\mathbf{n} \cdot \mathbf{J}_p = qv_{sr}(np - n_0 p_0)$$



These BCs suffer from the following problems:

- the equilibrium Fermi-level at the interface depends on doping type and concentration (i.e. no pinning)
- the surface charge doesn't change with recombination dynamics (e.g. no band-flattening with illumination)



- Fermi-level pins at the surface of many semiconductors
- Large number of defect states at surface
- Defect states act as traps and recombination centres
 - Trapped charge causes surface band bending
 - Surface pinning affects surface recombination
- In GaAs, Fermi-level pinning is attributed to two defect levels in the bandgap of the semiconductor

Fermi-level Pinning Model

$$Q_s = qN_{TD}(1 - f_{TD}) - qN_{TA}f_{TA}$$

$$f_T = \frac{\tau_p n + \tau_n p_1}{\tau_n(p + p_1) + \tau_p(n + n_1)}$$

$$R_{surf} = \frac{np - n_1 p_1}{\tau_p(p + p_1) + \tau_p(n + n_1)}$$

$$n_1 = N_C \exp\left(\frac{E_T - E_C}{kT}\right) \quad \tau_n = \frac{1}{N_T \sigma_n v_{th}}$$

$$p_1 = N_V \exp\left(\frac{E_V - E_T}{kT}\right) \quad \tau_p = \frac{1}{N_T \sigma_p v_{th}}$$

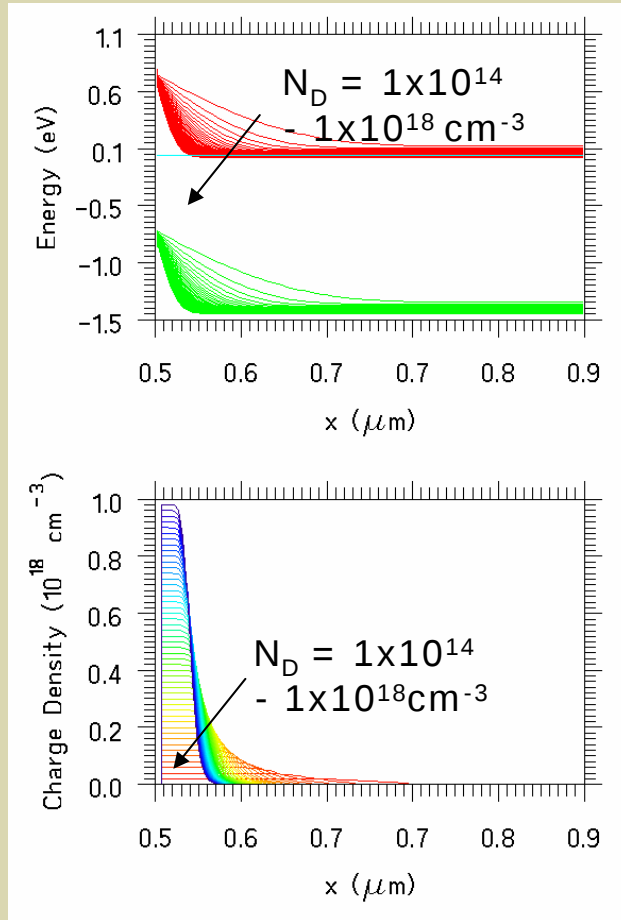
References: *W. E. Spicer et al., J. Vac. Sci. Technol. B, Vol. 6, pp. 1245-1251, 1988*

R. B. Darling, Phys. Rev. B Vol. 43, No. 5, pp. 4071-83, 1991

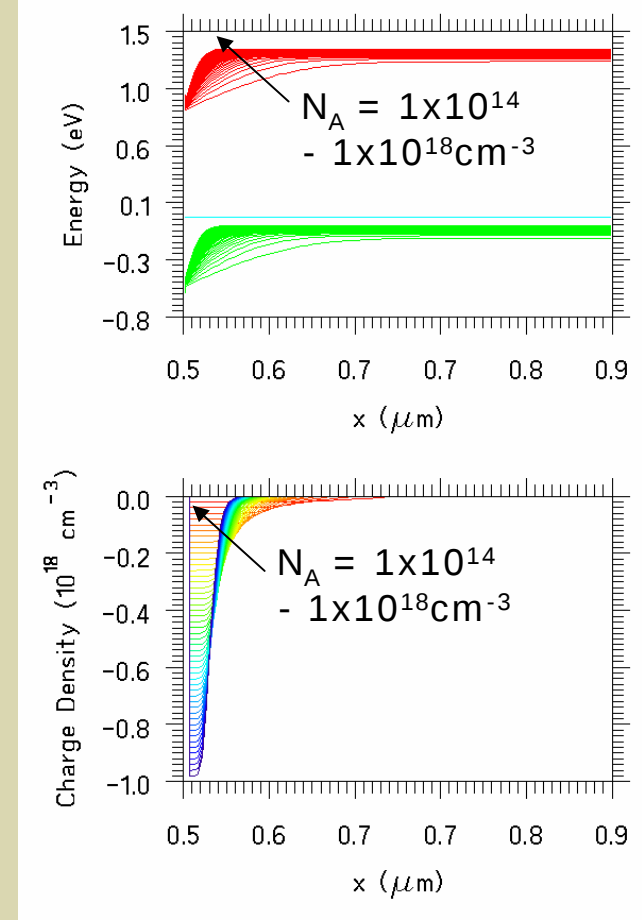
Surface Fermi-level pinning (Equilibrium)



- Surface band-bending of n- and p- GaAs at equilibrium



n-type



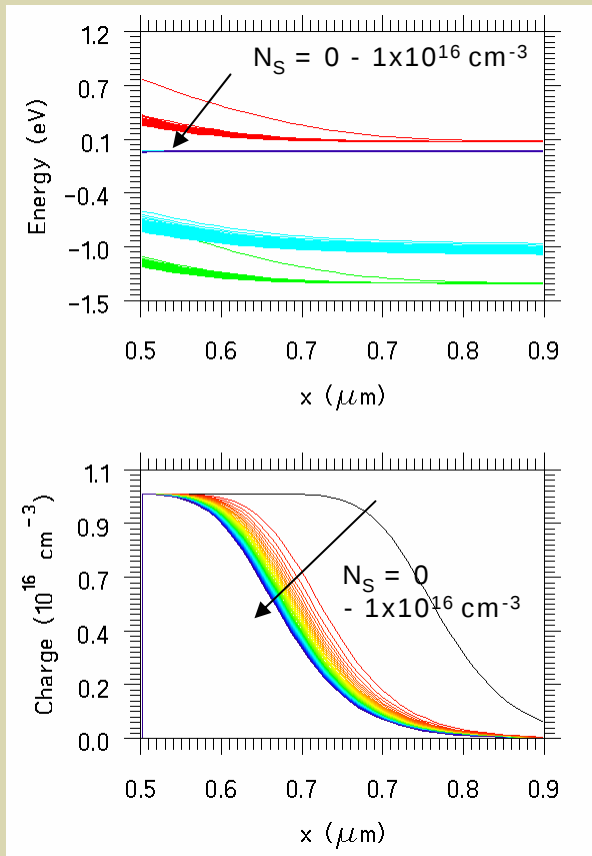
p-type

→ Surface Fermi-level nearly independent of dopant type / concentration.

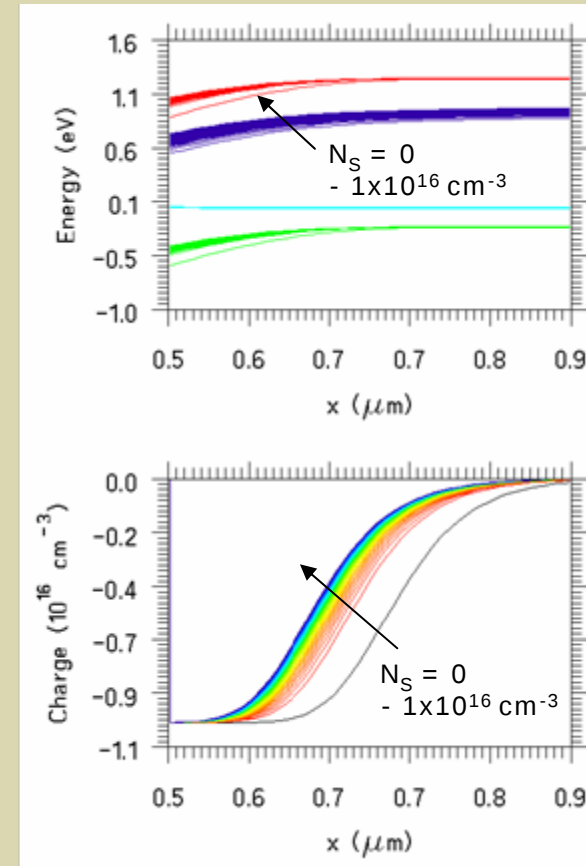
Surface Fermi-level pinning (Non-Equilibrium)



- Surface band-bending of n- and p- GaAs as a function of optical illumination
- $N_A / N_D = 1 \times 10^{16} \text{ cm}^{-3}$, $N_S = \Phi_s / v_g = 0 - 1 \times 10^{16} \text{ cm}^{-3}$

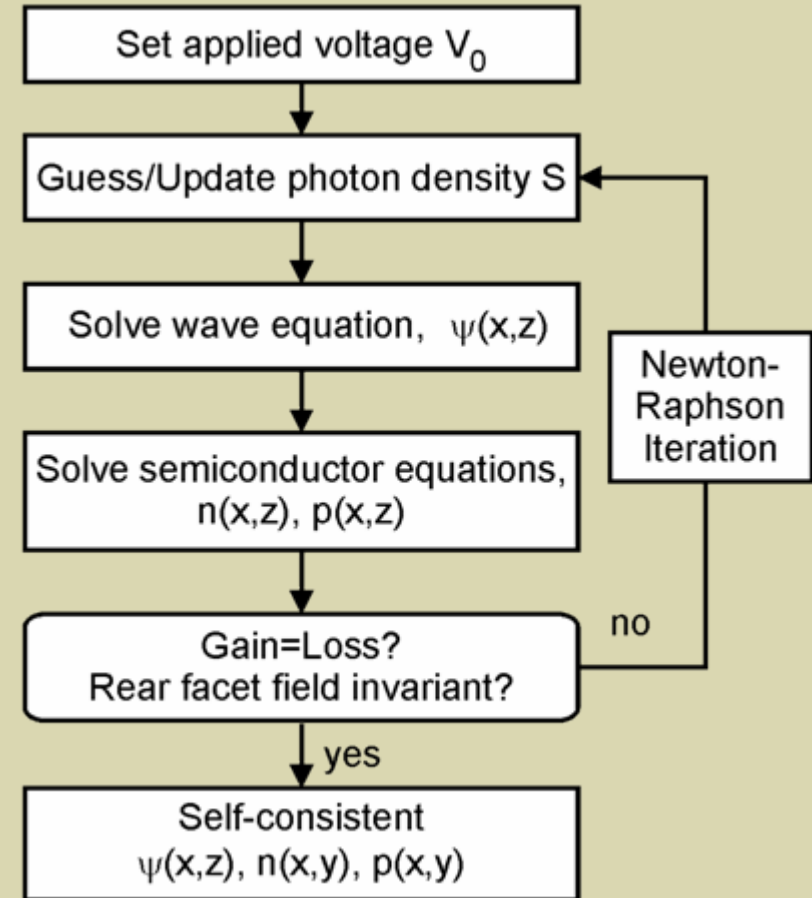
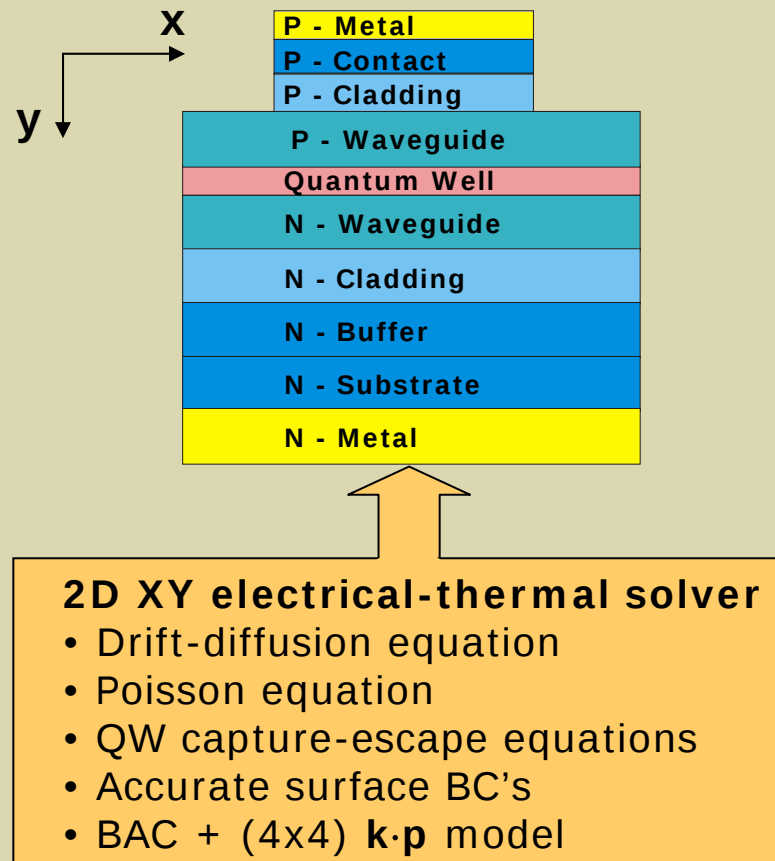


n-type

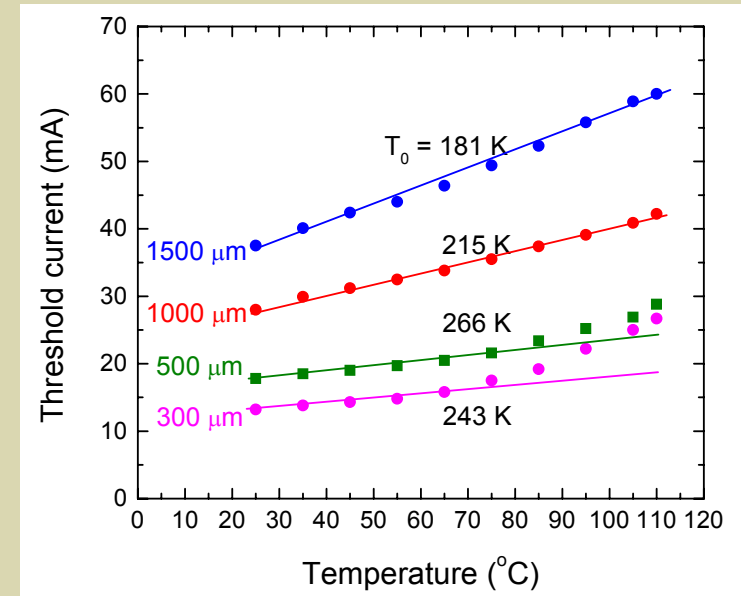
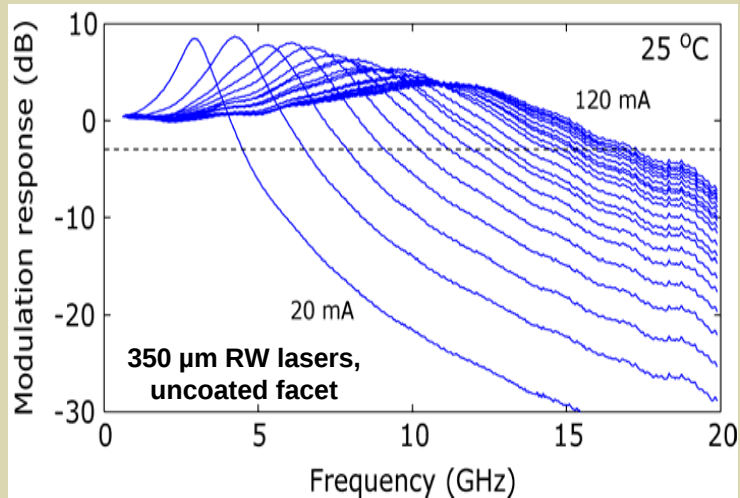


p-type

→ Illumination changes the depletion width and flattens the band-bending.



Dilute Nitride Lasers



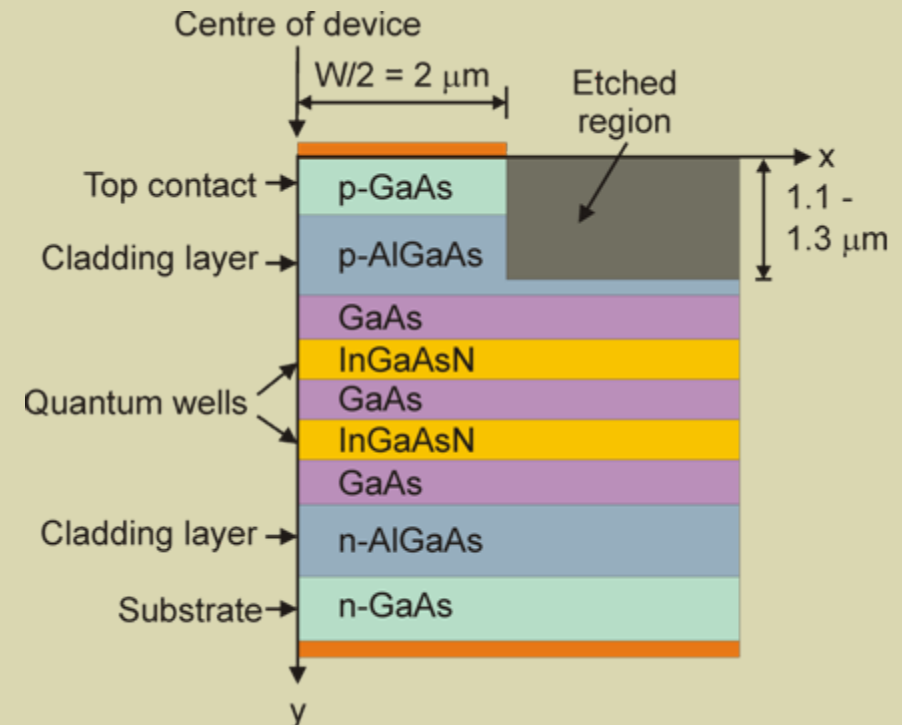
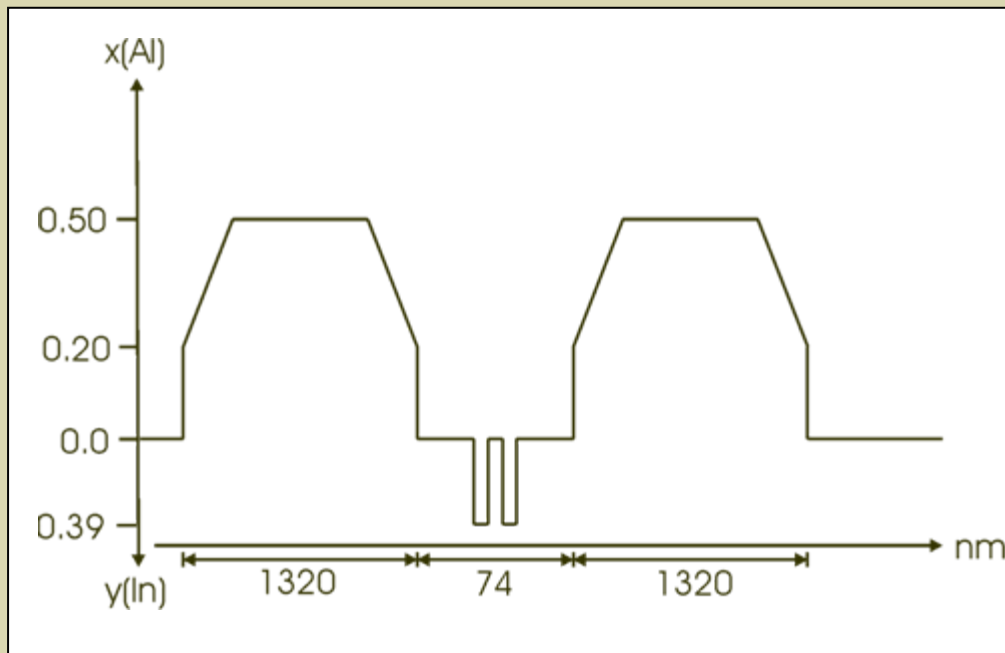
- Bandgap energy reduction – Longer wavelength
- Large conduction band offset – High T_0
- Low-cost alternative to InP for access networks
- 17 GHz maximum modulation bandwidth
- Characteristic temperature = 181-266 K (20-70 $^{\circ}\text{C}$)

Reference: Y.Q. Wei *et al.*, *Optics Express*, Vol. 14, pp. 2753-2759, 2006

Device Structure



- 7nm $\text{In}_{0.39}\text{Ga}_{0.61}\text{AsN}_{0.012}/\text{GaAs}$ DQW
- $4 \times 400 \mu\text{m}^2$ Ridge Waveguide



Reference: Y.Q. Wei et al., *Appl. Phys. Lett.*, Vol. 88, 051103, 2006.

Power-Current Characteristic



Surface trap parameters:

- Donor

- $E_D = 0.50 \text{ eV}$

- $N_{TD} = 1 \times 10^{13} \text{ cm}^{-2}$

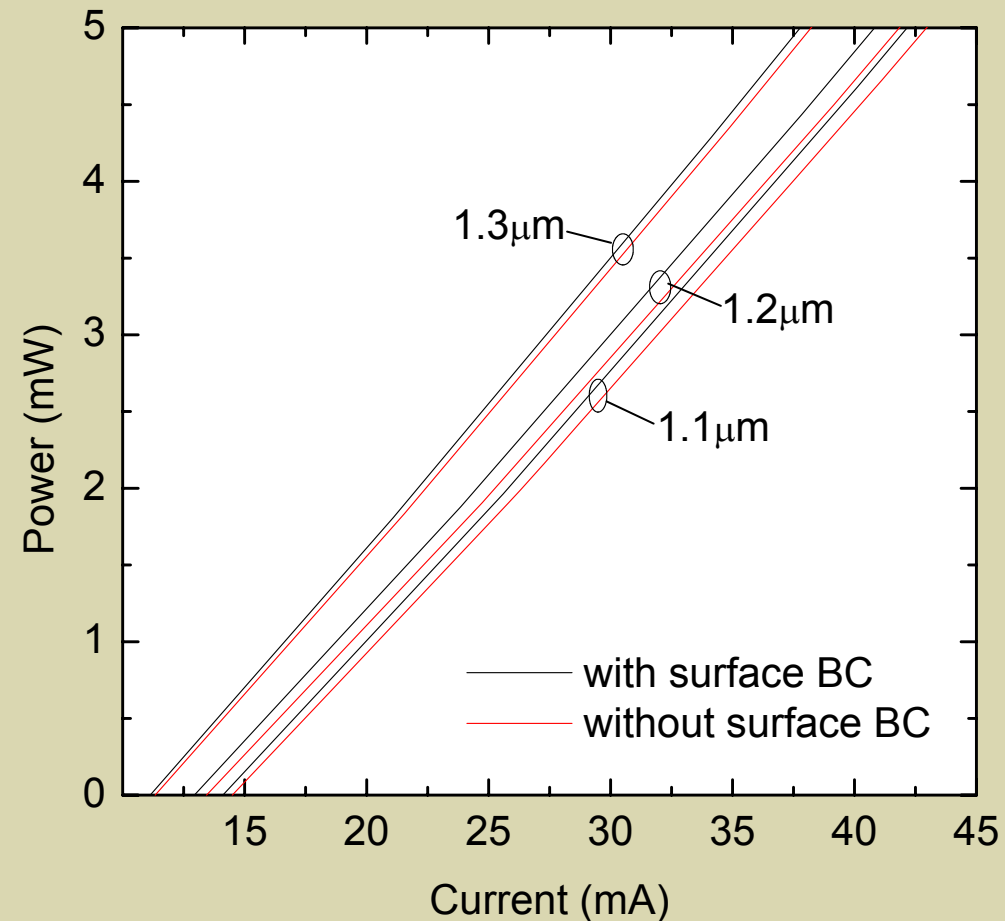
- $\sigma_{nD} = \sigma_{pD} = 1 \times 10^{-16} \text{ cm}^2$

- Acceptor

- $E_A = 0.75 \text{ eV}$

- $N_{TA} = 1 \times 10^{13} \text{ cm}^{-2}$

- $\sigma_{nA} = \sigma_{pA} = 1 \times 10^{-16} \text{ cm}^2$



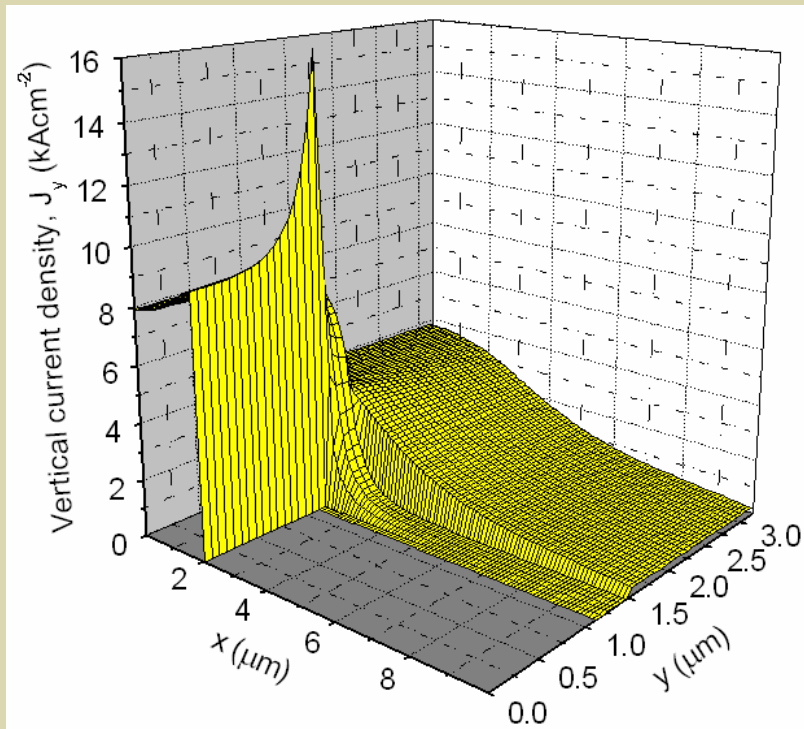
→ Surface band-bending reduces current spreading and threshold current

Vertical Current Density Distribution

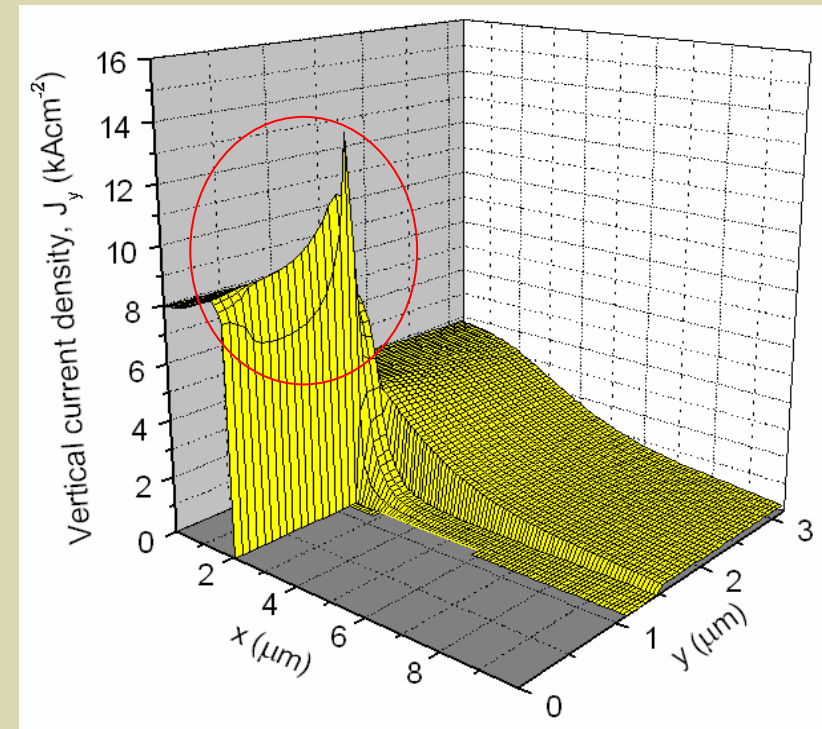


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- Etch depth = $1.2\mu\text{m}$



Without surface BC



With surface BC

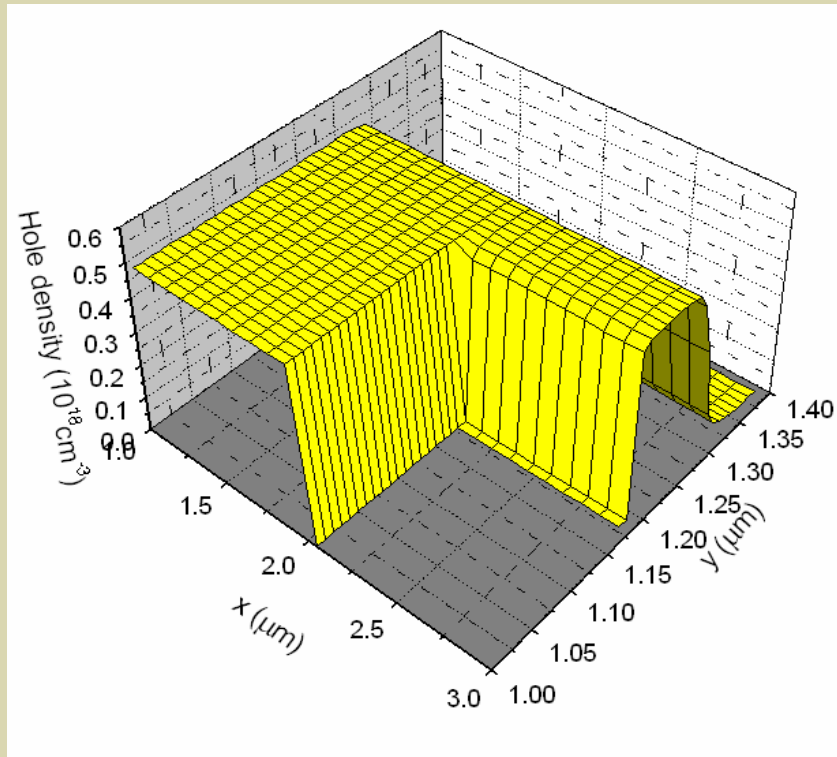
- ➔ Reduced current density at vertical edge of ridge
- ➔ Less current spreading means fewer carriers need to be supplied

Hole Density Distribution

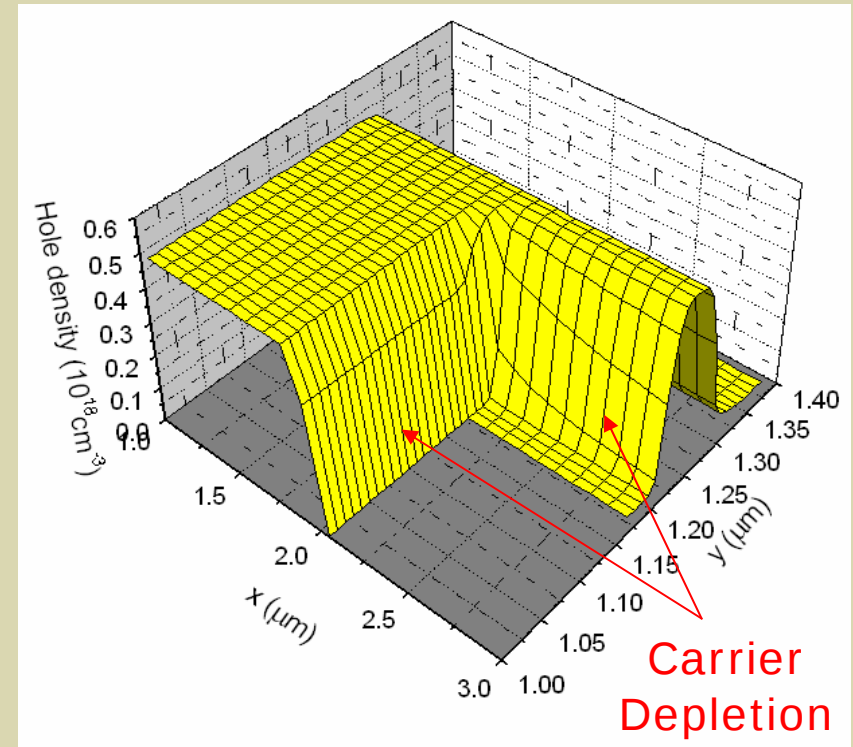


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- Etch depth = $1.2\mu\text{m}$



Without surface BC



With surface BC

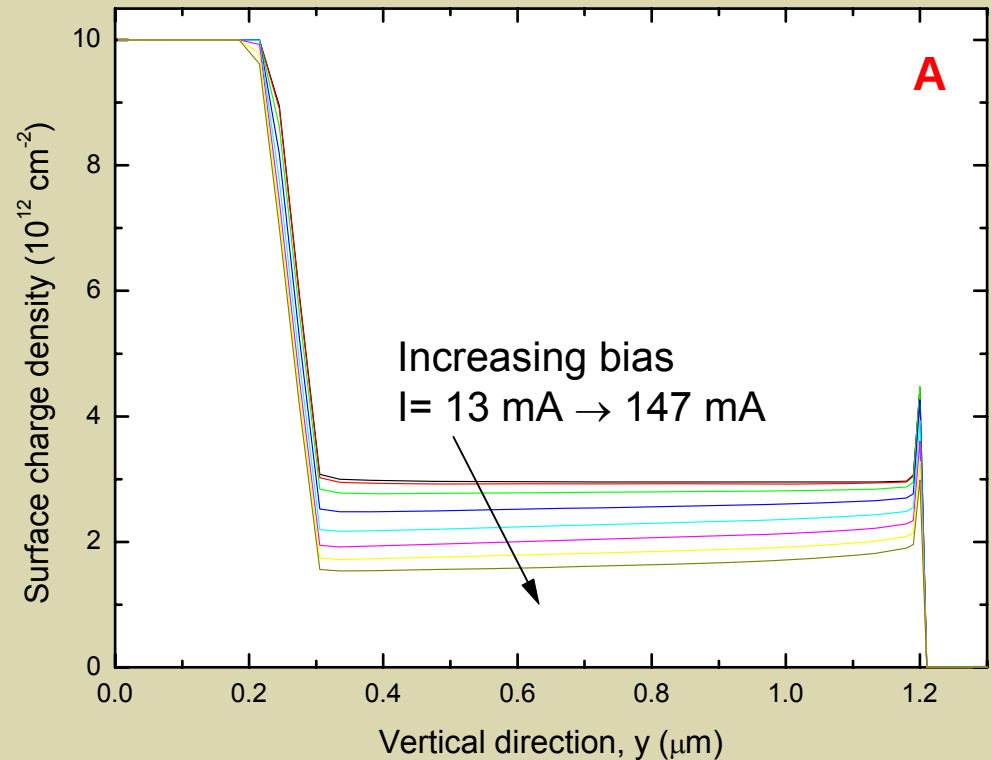
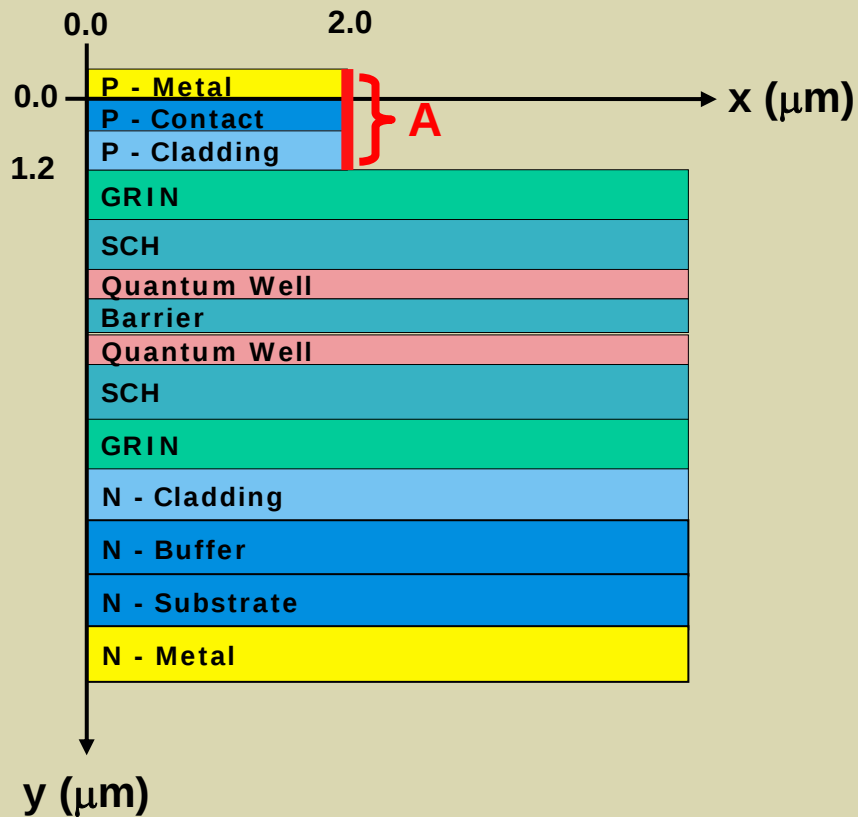
→ Surface Fermi-level pinning depletes the p-region beneath the etch

Surface Charge Density Distribution (Vertical Edge)



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• Etch depth = $1.2\mu\text{m}$



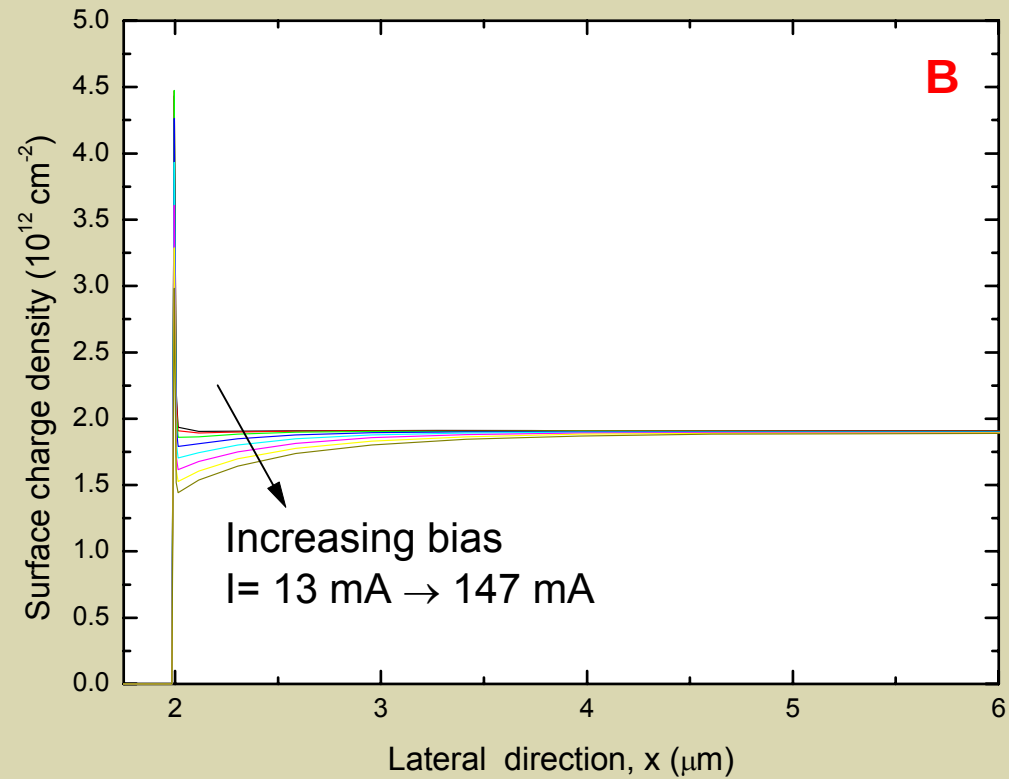
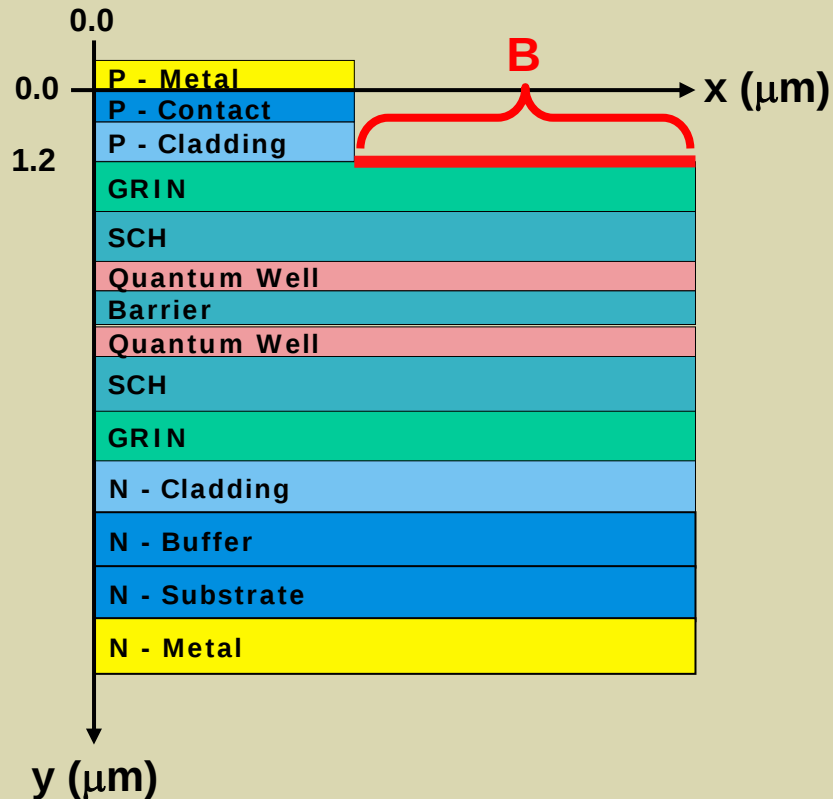
→ Surface charge (& depletion) depend on bias & position

Surface Charge Density Distribution (Lateral Edge)



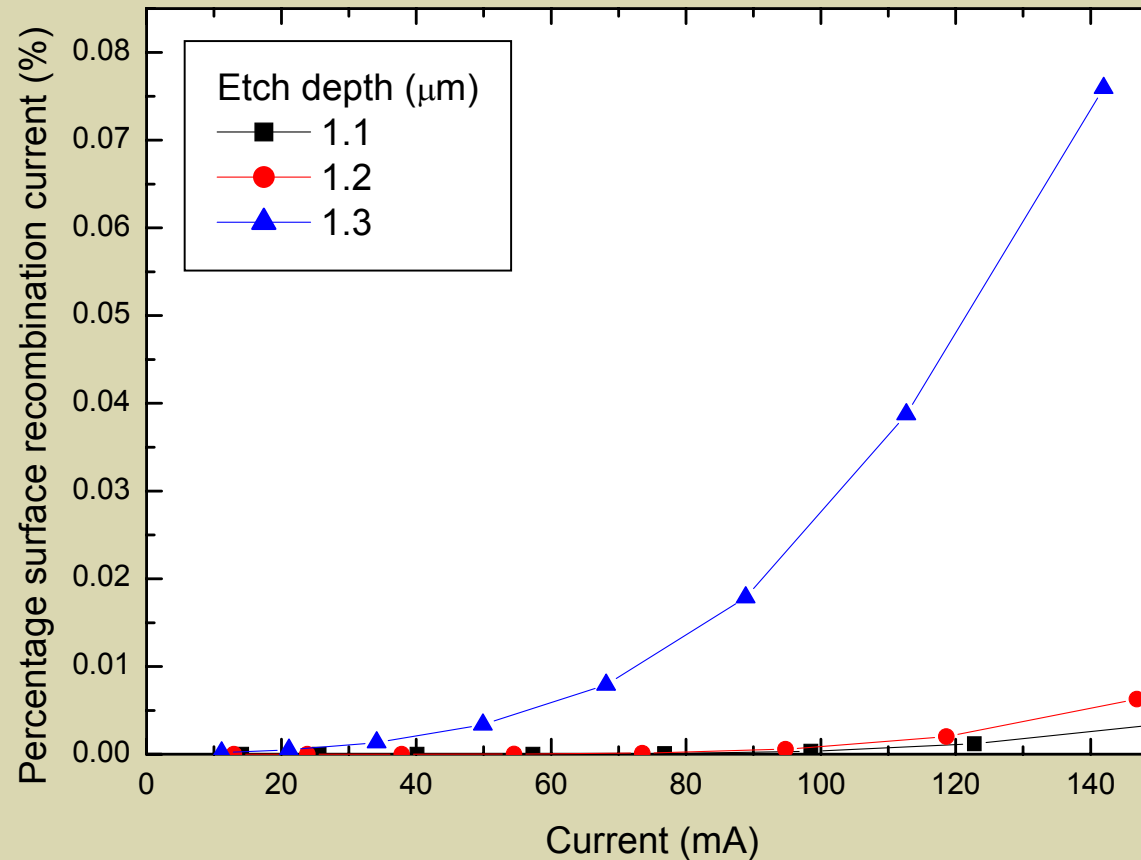
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• Etch depth = $1.2\mu\text{m}$



→ Surface depletion decreases with bias – lateral conductivity increases

Surface Recombination Current



- Surface recombination integrated over surface

→ Surface recombination current is small, but increases with etch depth and bias

Conclusions



- Accurate surface boundary condition implemented into a comprehensive laser diode simulator
- The assumption of a constant surface charge is inappropriate – distribution of charge is a nontrivial function of position and bias
- In ridge waveguide lasers, surface electrostatics in vicinity of the surface
- Surface recombination current is
- Surface recombination dynamics
- Surface recombination dynamics in laser structures
- Proper surface BC's do not need

